



1. Title:	Latest Development of EUV-Sources for Flexible Laboratory Use
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3. Abstract body:

AIXUV's EUV-LAMPs have already shown a long record of use and high flexibility in integration into systems like resist exposure tools, EUV-reflectometers, EUV-Microscopes, and in developing tools for source metrology. The focus on EUV-Lamp development at AIXUV was driven by the demands based on the applications and customer specific tools.

Low cost of ownership (e.g. 120 €/h) and operation (about 50 €/h) with  $> 500 \text{ J}/(2 \pi \text{ sr})$  / hour of in-band EUV) is achieved due to the long lifetime HCTP concept. More than 250 million pulses have been demonstrated with the system still under operation. AIXUV can supply EUV-Lamp systems for various power levels. To extend the power range AIXUV licensed the Xe-source technology from Philips EUV so that we now can offer EUV-Lamps of higher power and fully HVM-compatible small étendue.

The work at AIXUV was focused on the development of beamline solutions to deliver clean EUV-photons to the application and system integration.

In this paper we will discuss the latest developments and present recent results.